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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: LUIJKX et al.

Application No.: 10/748,849

Confirmation No.: 2810

Filed: December 31, 2003

Group No.: 2851

Examiner:

For: OPTICAL ATTENUATOR DEVICE, RADIATION SYSTEM AND LITHOGRAPHIC
APPARATUS THEREWITH AND DEVICE MANUFACTURING METHOD

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

SUPPLEMENTAL APPLICATION DATA SHEET
37 C.F.R. § 1.76(c)

The following information on the Application Data Sheet is changed as indicated:

BIBLIOGRAPHIC DATA

1. Applicant information is being modified and/or added.

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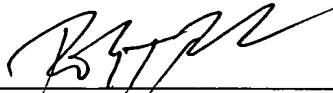
2. Assignee information is being modified.

The assignee(s) of this application is/are:

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Extent of interest of assignee in application: ENTIRE RIGHT, TITLE AND INTEREST

Date: July 6, 2004

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